

	Hit s	Search Text	DBs
45	24	((resist or photoresist) same (rotat\$4 or spin\$4coat\$4 or spin\$4 or spray\$5) same (thin\$4 or (reduc\$4 near9 thick\$4) or ((uniform\$4 or minimis\$4 or desired or predetermin\$3) near6 thick\$5)) same (adjust\$4 or vary or var\$4) same (thickness or layer)) and ((resist or photoresist or imaging) same transmiss\$3 same (thickness or layer or coating or film)) and (((absorption near9 coefficient) or percentage or amount or (high near9 absorption)) same (photoresist or resist))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
46	0	((resist or photoresist) same (rotat\$4 or spin\$4coat\$4 or spin\$4 or spray\$5) same (thin\$4 or (reduc\$4 near9 thick\$4) or ((uniform\$4 or minimis\$4 or desired or predetermin\$3) near6 thick\$5)) same (adjust\$4 or vary or var\$4)) and ((resist or photoresist or imaging) same transmiss\$3 same (thickness or layer or coating or film)) and (((absorption near9 coefficient) or (high near9 absorption)) same (photoresist or resist) same ((metallocene near9 polymer) or fluorine or antimon\$5 or fluoro\$3polymer or cesium or bismuth))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB